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PATENT ABSTRACTS OF JAPAN

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(71) Applicant: NEC CORP

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(74) Representative:

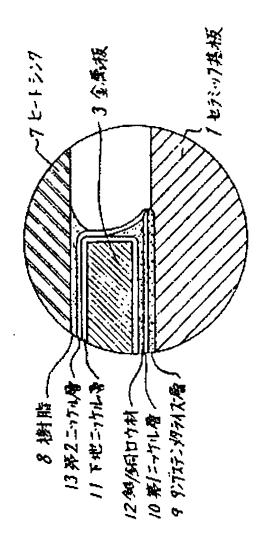
(54) **SEMICONDUCTOR** DEVICE

(57) Abstract:

PURPOSE: To improve a bonding strength by a method wherein a nickel layer is made to be employed as a metallic face to which a heat sink is to be bonded.

CONSTITUTION: A metallic plate 3 is so brazed as to cover a throughnole provided to the center of a ceramic substrate 1 of a semiconductor device provided with a heat sink, a semiconductor element is fixed to the recessed part of the ear of the plate 3, and a heat sink is oonded to the top surface of the plate 3. The metallic plate 3 provided with a primary nickel layer 11 on it is orazed to a first nickel layer 10, which is formed on a tungsten netallized layer 9 built on the substrate 1, using a silver/copper orazing material 12, and a second nickel layer 13 and a gold plated layer are formed through electroplating, then the gold plated layer is removed and a heat sink 7 is made to be directly bonded to the nickel layer 13 using a resin 8. In this process, a adhesive seal or a film material is applied onto the part of the nickel layer 13 to which the heat sink 7 is made to be bonded and then a gold plating is performed, then a required part of the nickel layer 13 is made to be exposed. Or a gold plating is performed onto the whole face, and then gold plated on the required part is removed through etching.

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Title:

JP1073750A2: SEMICONDUCTOR DEVICE

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Country:

JP Japan

Kind:

Inventor(s):

MIYAMOTO TAKASHI

Applicant/Assignee:

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March 20, 1989 / Sept. 16, 1987

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H01L 23/34; H01L 23/40;

Priority Number(s):

Sept. 16, 1987 <u>JP1987000233108</u> Aug. 31, 1999 <u>JP1999000245110</u>

Abstract:

Purpose: To improve a bonding strength by a method wherein a nickel layer is made to be employed as a metallic face to which a heat sink is to be bonded.



Constitution: A metallic plate 3 is so brazed as to cover a throughhole provided to the center of a ceramic substrate 1 of a semiconductor device provided with a heat sink, a semiconductor element is fixed to the recessed part of the rear of the plate 3, and a heat sink is bonded to the top surface of the plate 3. The metallic plate 3 provided with a primary nickel layer 11 on it is brazed to a first nickel layer 10, which is formed on a tungsten metallized layer 9 built on the substrate 1, using a silver/copper brazing material 12. and a second nickel layer 13 and a gold plated layer are formed through electroplating, then the gold plated layer is removed and a heat sink 7 is made to be directly bonded to the nickel layer 13 using a resin 8. In this process, a adhesive seal or a film material is applied onto the part of the nickel layer 13 to which the heat sink 7 is made to be bonded and then a gold plating is performed, then a required part of the nickel layer 13 is made to be exposed. Or a gold plating is performed onto the whole face, and then gold plated on the required part is removed through etching.

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DERABS G2001-184498

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